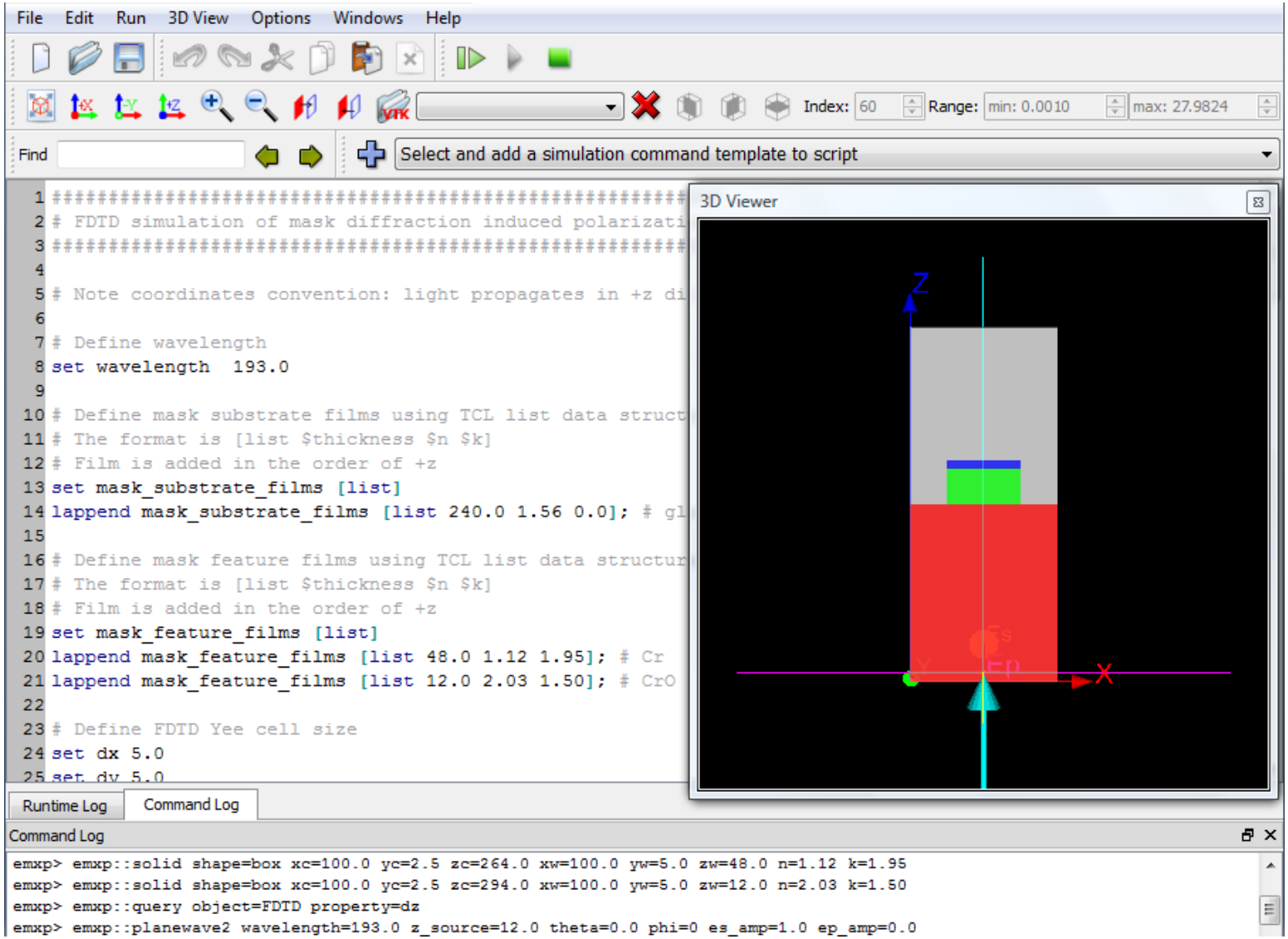
3D Mask Scattering Induced Polarization

Simulation Setup

(Based on Karsten Bubke et al., “Investigation of Polarization Effects on new Mask Materials,” Optical Microlithography XVIII, Proceedings of SPIE Vol.5754, 2005)



EM EXPLORER At The Edge

Degree of Polarization

$$DOP = \frac{\eta_{TE} - \eta_{TM}}{\eta_{TE} + \eta_{TM}}$$

where η = diffraction efficiency